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			U.S. PAT	ENT DOCUMENTS	
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M	CA	"Etchless Fabrication of Slab Photonic Crystals in Silicon", Janusz Murakowski et al, CLEO Conference Paper, May 19-25, 2002, Long Beach, California.							
M	CB	"Etchless Fabrication of Phnotonic Crystals in Silicon", Janusz Murakowski, et al., American Vacuum Society, J. Vac. Sci. Technology Bulletin 20(5), Sep/Oct 2002.							

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